

CURRENT PROFILE CONTROL VIA ACTIVE T_e CONTROL IN DIII-D

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T_e FEEDBACK IS MOST EFFECTIVE MEANS OF CONTROLLING CURRENT PROFILE DURING THE CURRENT RAMP

- Current density consists of inductive and non-inductive parts:

$$J = J_{\text{Ohm}} + J_{\text{non-ind}}$$

$$J_{\text{Ohm}} = \sigma E_{\parallel}$$

$$J_{\text{non-ind}} = J_{\text{BOOT}} + J_{\text{ECCD}} + J_{\text{NBCD}} + \dots$$

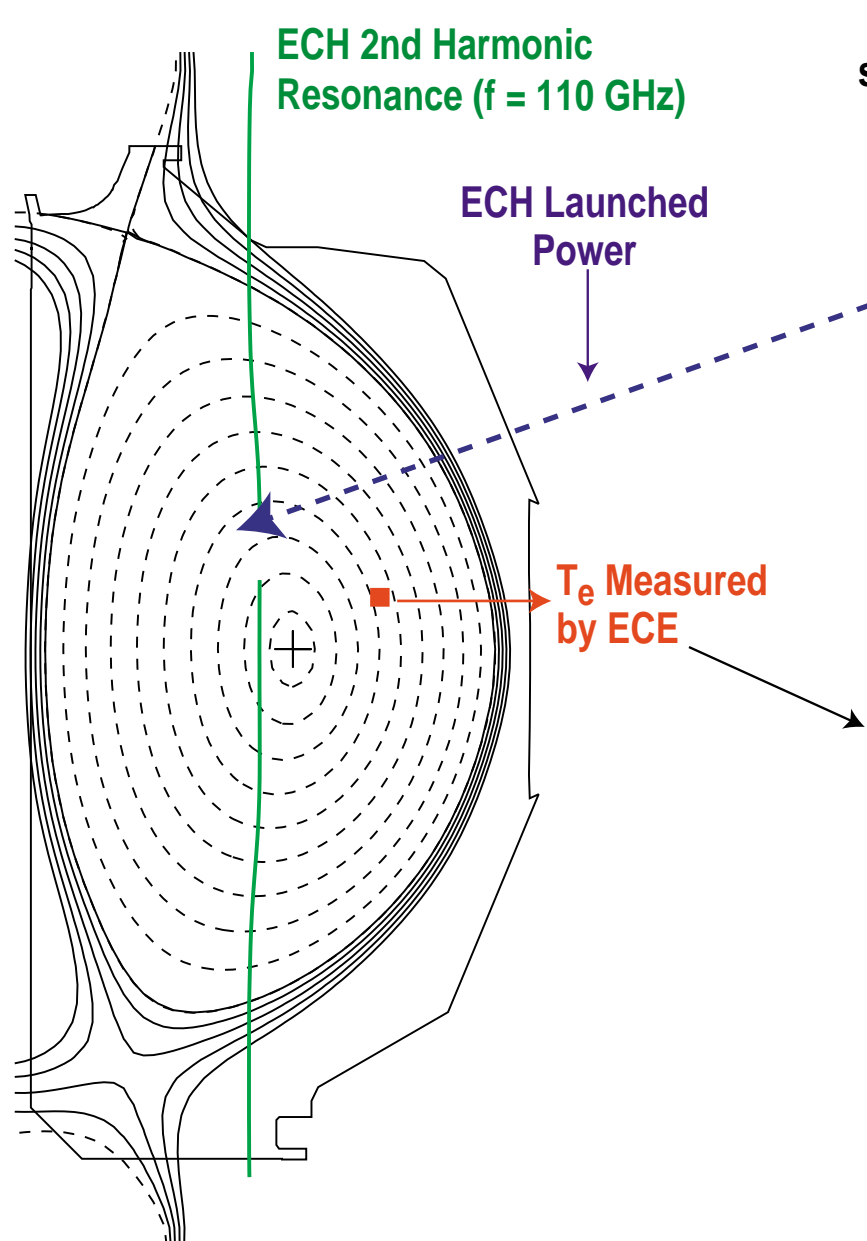
- Non-inductive sources are either small or inefficient at low β or low $T_e \Rightarrow$ can't be used early in current ramp

- Ohmic current evolution governed by

$$\frac{\partial E_{\parallel}}{\partial t} = \frac{1}{\mu_0 \sigma} \nabla^2 E_{\parallel} \quad \text{where} \quad \sigma \propto \frac{T_e^{3/2}}{Z_{\text{eff}}}$$

- Without external intervention, E_{\parallel} penetrates rapidly resulting in $q_0 \cong 1$ at end of current ramp
- Controlling T_e allows a **direct**, reliable means for controlling current profile evolution

ACTIVE T_e CONTROL MADE POSSIBLE BY UPGRADES TO DIII-D ECH SYSTEMS, PLASMA CONTROL SYSTEM, AND ECE DIAGNOSTIC



Gyrotrons (power separately controlled)

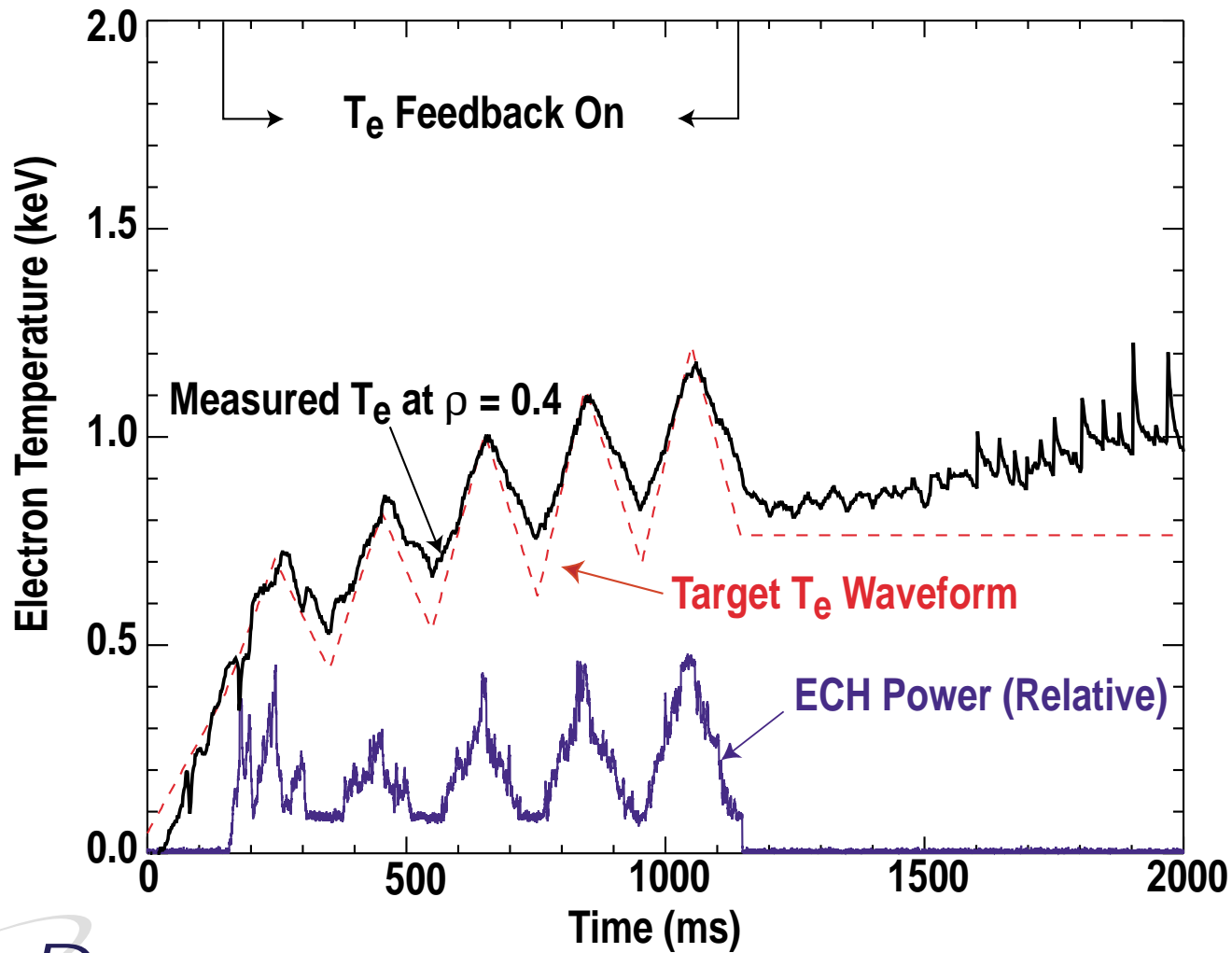


Plasma Control System (PCS)

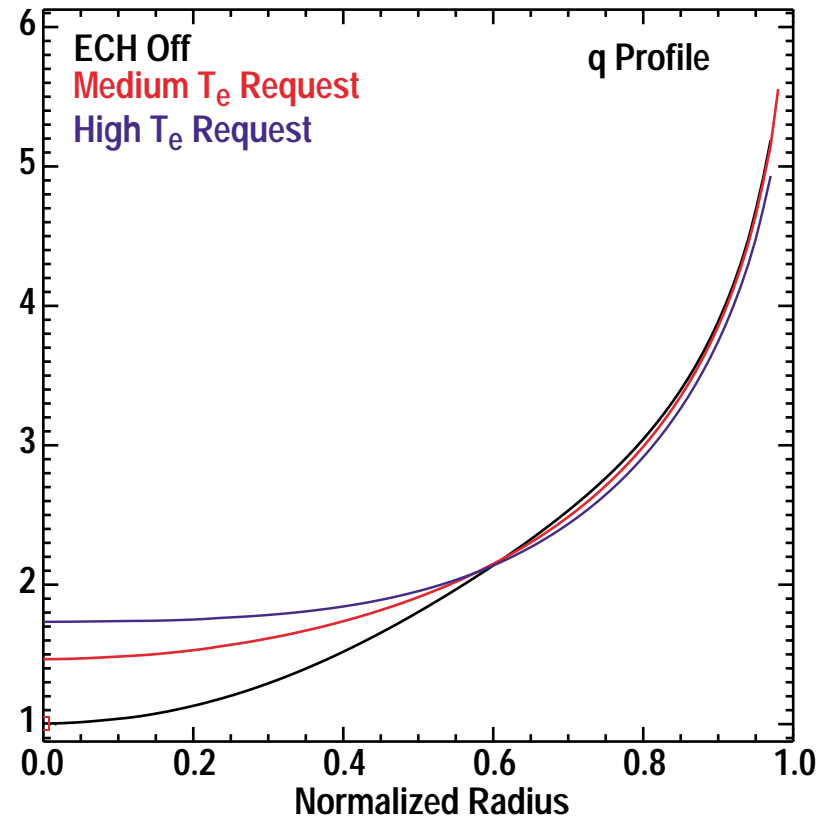
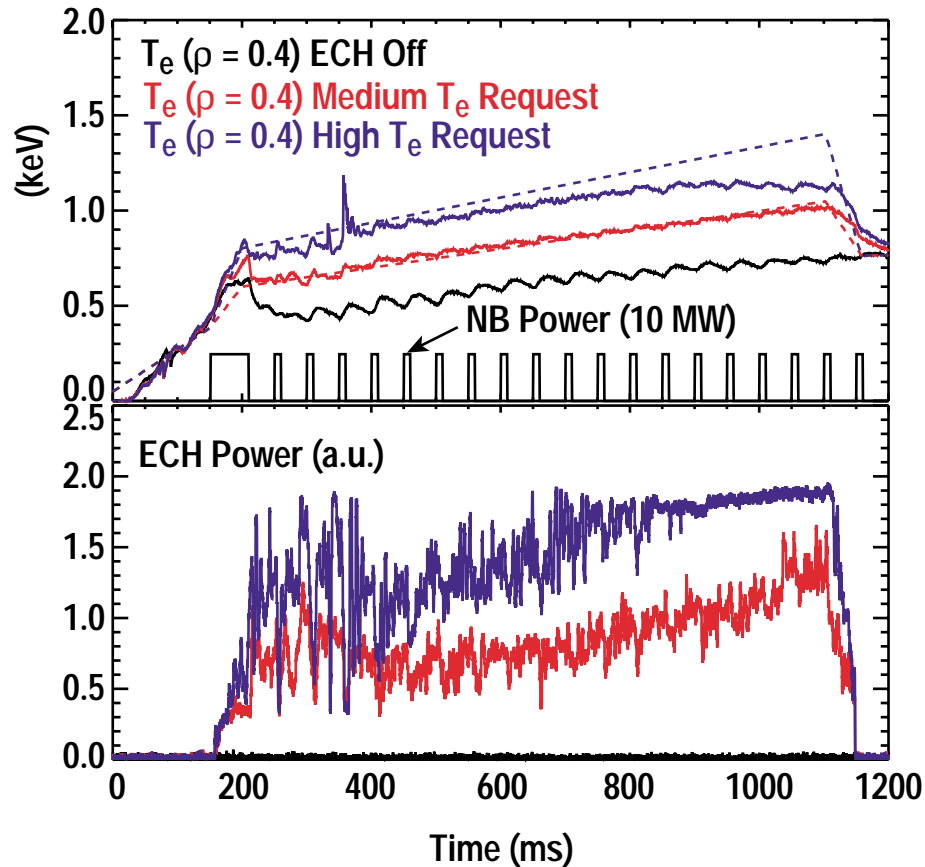


FINE CONTROL OF T_e EVOLUTION HAS BEEN DEMONSTRATED

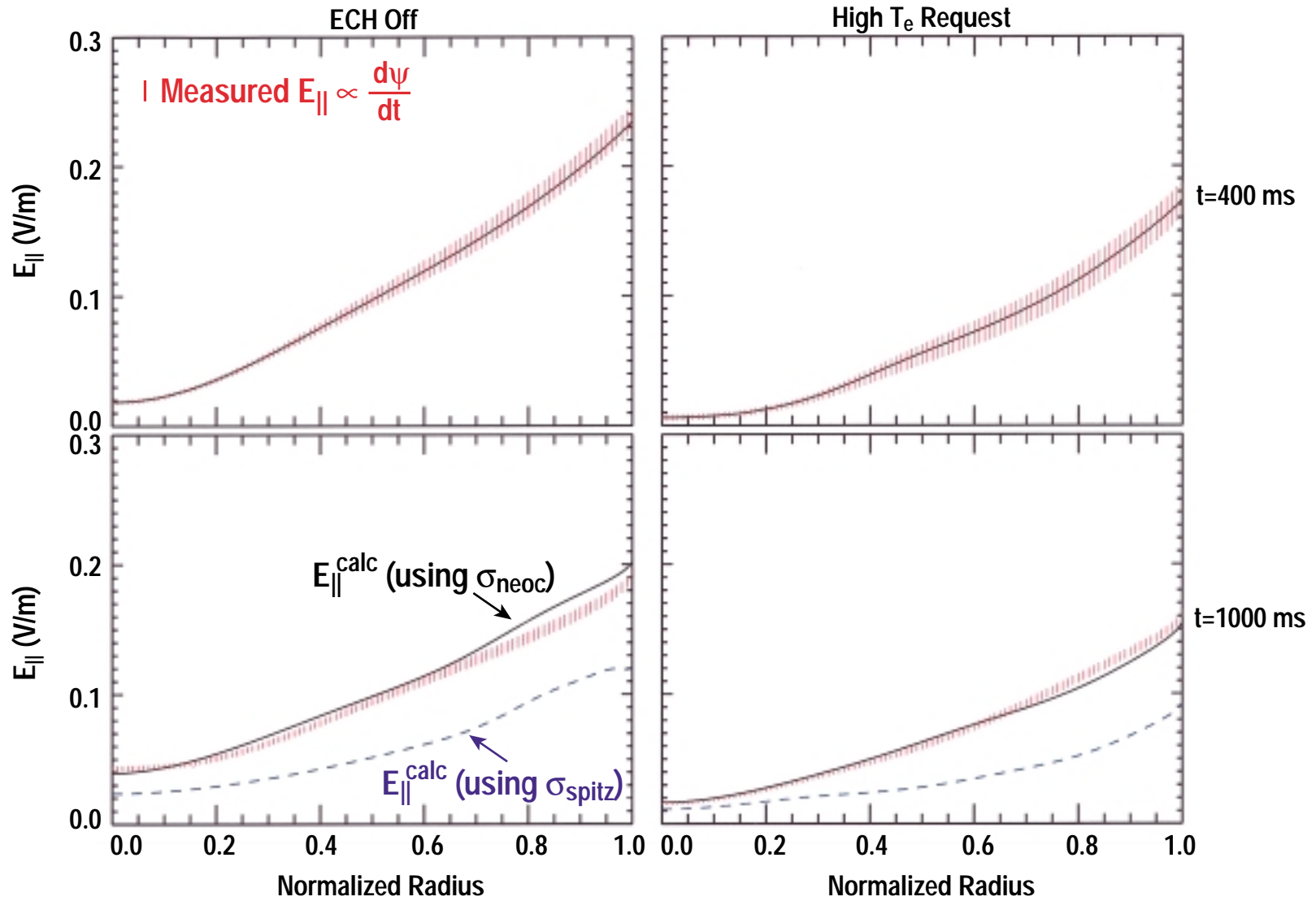
- ECH deposition at $\rho = 0.4$
- PCS using ECE measurement at $\rho = 0.4$ as sensor



STUDIES SHOW THAT SYSTEMATICALLY INCREASING T_e RESULTS IN LESS CURRENT PENETRATION



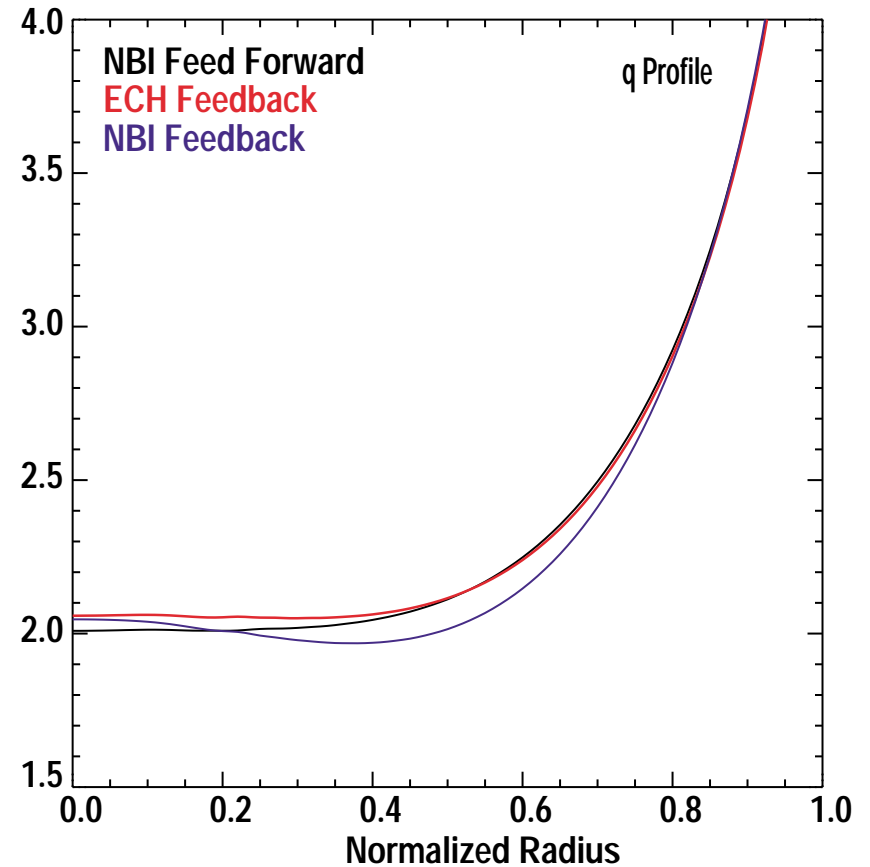
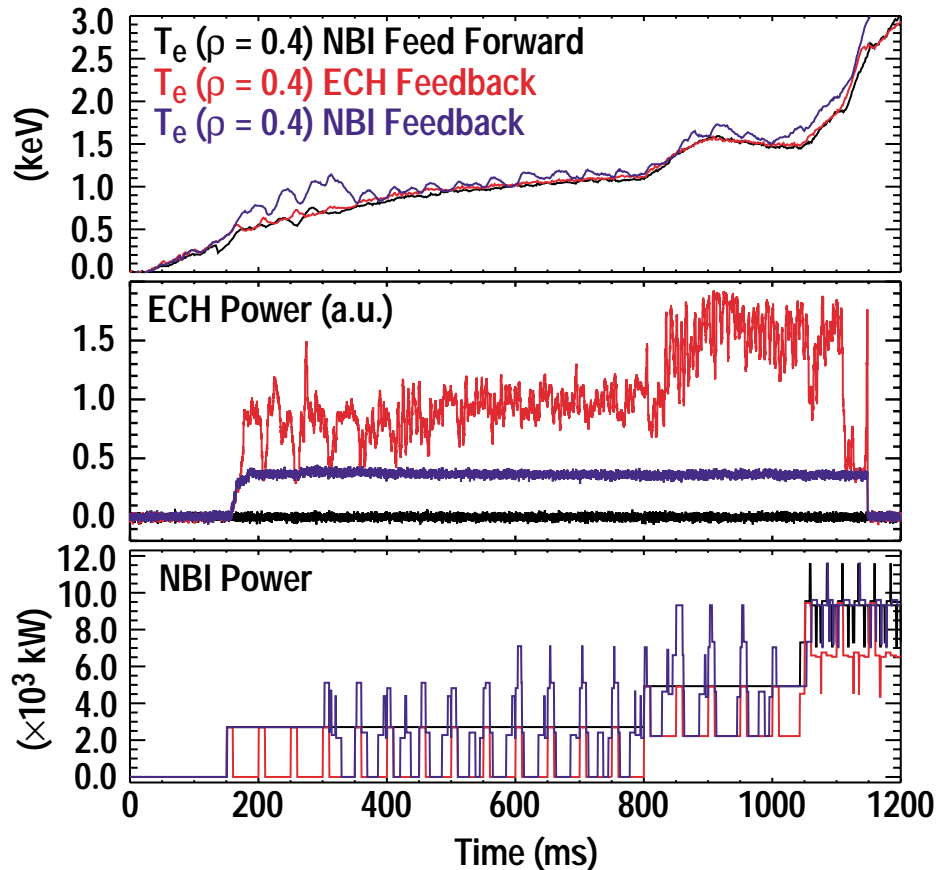
MEASURED E_{\parallel} EVOLUTION CONSISTENT WITH NEOCLASSICAL RESISTIVITY



USING T_e FEEDBACK, SIMILAR CURRENT PROFILE EVOLUTION PRODUCED BY VARIETY OF ACTUATORS

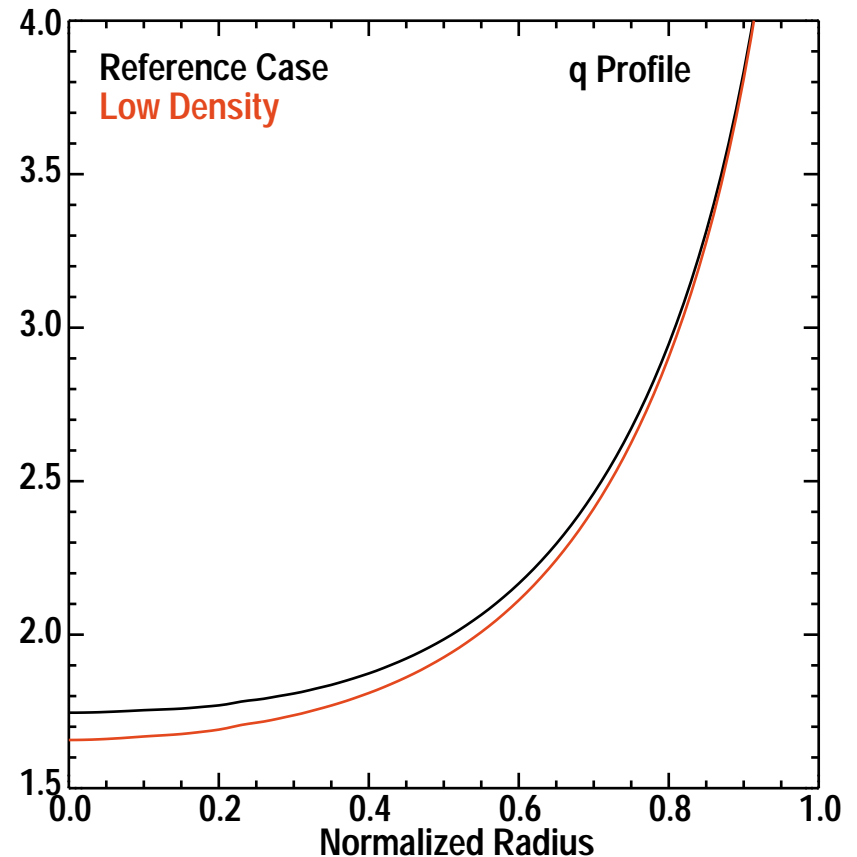
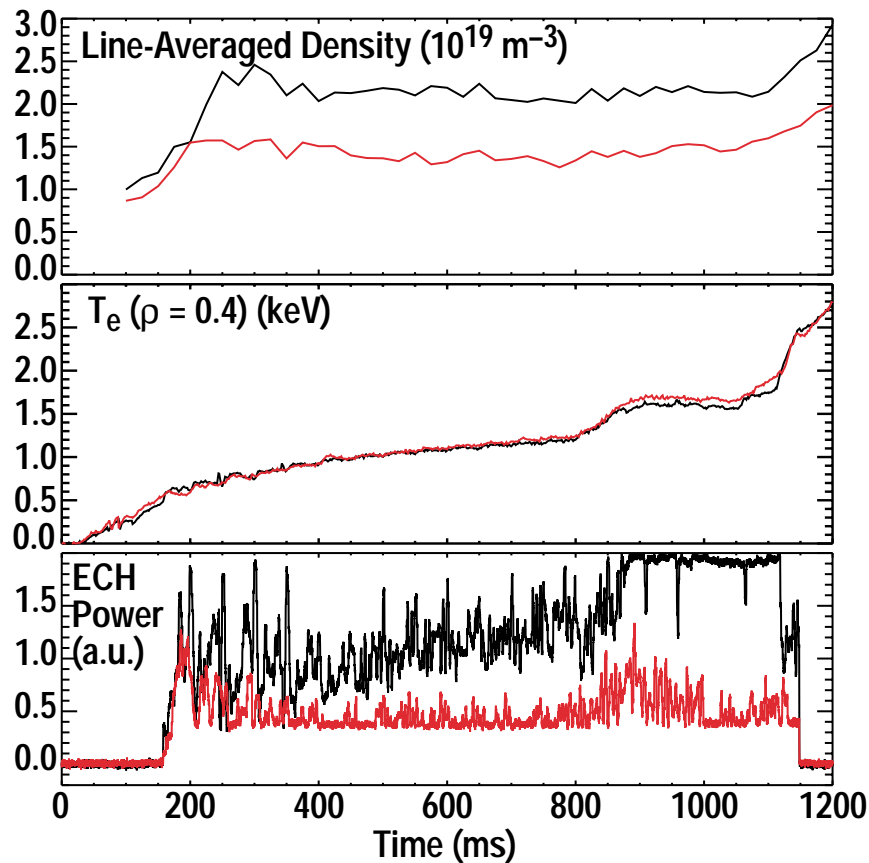
- Same T_e evolution gives ...

similar q profile at end of I_p ramp



- Differences due to non-inductive sources (e.g. NBCD in neutral beam case)

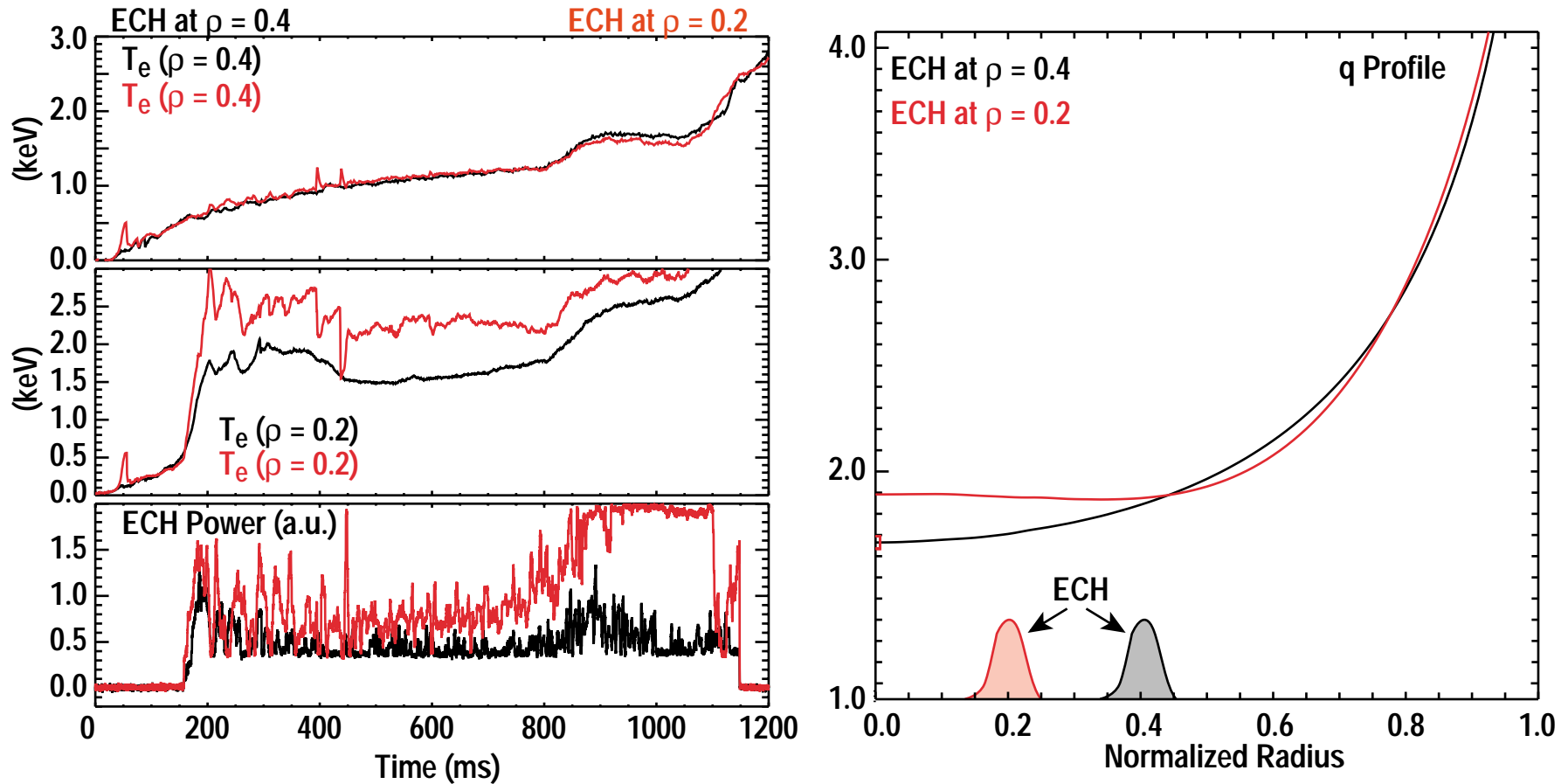
T_e FEEDBACK ALLOWS DECOUPLING OF CURRENT PROFILE AND EVOLUTION FROM PLASMA DENSITY



- Difference due to reduced bootstrap current at lower density
- Benefit: Reduced gas fueling during I_p ramp leads to less wall fueling and lower H-mode density

CHANGING ECH DEPOSITION LOCATIONS ALTERS CURRENT PROFILE EVOLUTION

- PCS using ECE signal at $\rho = 0.4$ as sensor



- As expected, higher central T_e leads to more inverted q profile

SUMMARY

- Active T_e control has been demonstrated on DIII-D. Made possible by upgrades to several systems
 - Plasma Control System
 - ECH
 - ECE Diagnostic
- Systematic variation in T_e during current ramp shown to slow current penetration
 - Measured $E_{||}$ evolution agrees with that expected from neoclassical resistivity
- Similar q profiles at end of current ramp can be produced in wide variety of conditions and with different actuators
 - Opens up many new possibilities for Advanced Tokamak research